

2) a sulfonium salt photoacid generator compound having a cation component that is substituted with one or more of a moiety that has at least 4 carbon atoms and is selected from optionally substituted alkyl, optionally substituted alkenyl, optionally substituted alkynyl, optionally substituted heteroalkyl, optionally substituted heteroalkenyl or optionally substituted heteroalkynyl,

and the photoacid generator compound having an anion compound that is i) an arylsulfonate counter anion substituted with one or more electron-withdrawing groups or ii) an alicyclic moiety that is substituted with one or more electron-withdrawing groups.; and

3) a non-hydroxylic solvent, and wherein the composition contains less than about 10 weight percent, based on total weight of the composition, of a hydrolyic solvent.

44. The photoresist of claim 43 wherein the photoacid generator is a triaryl sulfonium salt that has one or more aryl substituted by the moieties.

45. The photoresist of claim 43 wherein the photoacid generator is a triphenyl sulfonium salt that has one or more phenyl groups substituted by the moieties.

46. The photoresist of claim 43 wherein the photoacid generator is substituted with a moiety having 5 or more carbon atoms.

47. The photoresist of claim 43 wherein the photoacid generator is substituted with a moiety having 6 or more carbon atoms.

48. The photoresist of claim 43 wherein the photoacid generator is substituted by one or more alkoxy groups.

49. The photoresist of claim 43 wherein the photoacid generator is substituted by one or more alkyl groups.